

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

<p>In re application of: MARAKHTANOV et al Serial No.: 10/808,795 Filed: March 24, 2004 Title: PLASMA PROCESSING SYSTEM CONTROL</p>	<p>Group Art Unit: 2821 Examiner: UNASSIGEND Docket: P1220/LMRX-P030 Confirmation No.: 6020</p>
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INFORMATION DISCLOSURE STATEMENT

US PATENT DOCUMENTS

Examiner Initials	Cite No.	Document Number	Publication Date	Name of Patentee or Applicant	Reference to Related Case
		US-5933314	1999-08-03	Lambson et al.	

FOREIGN PATENT DOCUMENTS

Examiner Initials	Cite No.	Document Number	Publication Date	Applicant	Reference to Related Case	T

OTHER DOCUMENTS

Examiner Initials	Cite No.		T
		Kawamura et al., "Ion energy distributions in RF sheaths; review, analysis and simulation", 1990, <i>Plasma Sources Science Technology</i> 8, R45-R64.	
dv		Lieberman et al., "Principles of Plasma Discharges and Materials Processing", 1994, New York, John Wiley and Sons, Inc..	

Examiner Signature	David vn	Date Considered	9/3/05
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